

Tool Code	PROCESS	EQUIPMENT	MANUFACTURER	MODEL	WAFER SIZE	VINTAGE
7373	TEST	TESTER	ADVANTEST (Verigy)	93000 C200e	-	2007
7655	TEST	TESTER	Agilent	4072A	-	2004
7693	TEST	TESTER	Agilent	4073A	-	2002
7893	TEST	TESTER	Agilent	4073A	-	2004
8409	TEST	PARAMETRIC TESTER	Agilent	4142B	-	2000
8411	CVD	PLASMA CVD	Applied Materials	P-5000	150	1990
7424	CVD	PLASMA CVD	ASM	Eagle10	200	1998
7104	CVD	PLASMA CVD	ASM	Eagle10 TRIDENT	150	2007
6922	CVD	PLASMA CVD	ASM	Eagle10 TRIDENT	200	2003
7719	ASHER	ASHER	Canon	MAS-8200	200	-
7819	PVD	SPUTTERING SYSTEM	CANON ANELVA	I-1080PVD	200	2001
8273	PVD	SPUTTERING SYSTEM	CANON ANELVA	ILC-1080	200	2003
7921	TEST	WAFER PROBER	CASCADE	Summit12862	-	2001
7641	DICING	DICER	DISCO	DAD3350	200	-
7642	DICING	AUTOMATIC CLEANING SYSTEM	DISCO	DCS141	200	-
7640	DICING	DICER	DISCO	DFD-2S/8	200	-
7837	DICING	DICER	DISCO	DFD6240	200	2004
7089	TEST	LASER REPAIR SYSTEM	ESI	ESI 9350	200	2004
8392	METROLOGY	FILM STRESS MEASUREMENT	FSM	FSM-128	200	2001
8134	METROLOGY	FILM STRESS MEASUREMENT	FSM	FSM-128	200	-
7653	MARKING	Wafer Marker	GSI	MARK-EM	150	2002
7517	ETCH	ION MILLING	HITACHI	IML-6-1	150	1997
8163	OTHERS	AIR DUST MONITOR	HITACHI	TS-3700	200	1990
8283	OTHERS	AIR DUST MONITOR	HITACHI	TS-6500	200	2000
7960	METROLOGY	FIB	Hitachi High-Tech	FB2100	-	2004
7733	METROLOGY	FIB	Hitachi High-Tech	FB-2100	-	2002
7959	METROLOGY	REVIEW SEM	Hitachi High-Tech	HD2700B	-	2010
7768	METROLOGY	NANO PROBER	Hitachi High-Tech	NE4000	-	2011
7852	METROLOGY	REVIEW SEM	Hitachi High-Tech	S-3400N	-	2010
7748	METROLOGY	REVIEW SEM	Hitachi High-Tech	S-3700N	-	2012
7961	METROLOGY	REVIEW SEM	Hitachi High-Tech	S-4800(Type I )	-	2004
7758	METROLOGY	MICROSCOPE	Hitachi High-Tech	TM3000	-	2012
7924	INSPECTION	VISUAL INSPECTION	INSPEC	LF2000	-	2005
7925	INSPECTION	VISUAL INSPECTION	INSPEC	LF2000	-	2005
7901	METROLOGY	FILM THICKNESS MEASUREMENT	JVS	JVX5200T	300	2005
7563	MARKING	LASER MARKER	KEYENCE	ML-Z9500/9510	-	2008
7594	METROLOGY	REVIEW SEM	KLA-Tencor	eDR5210S	300	2011
7857	METROLOGY	FILM THICKNESS MEASUREMENT	KLA-Tencor	UV1280SE	200	2003
8451	METROLOGY	LIFETIME MEASURING	KOBELCO	LTA-500	150	1996
7220	METROLOGY	LIFETIME MEASURING	KOBELCO	LTA-550	200	1991
7420	FURNACE	FURNACE_LP-CVD	KOKUSAI ELECTRIC	DJ-1206V-DF(ULT/SiO2)	300	2007
7858	METROLOGY	RESISTIVITY TEST SYSTEM	KOKUSAI ELECTRIC	VR-120/08S	200	2003
7669	BONDING	WIRE BONDER	Kulicke & Soffa	Maxum ultra	-	2008
7670	BONDING	WIRE BONDER	Kulicke & Soffa	Maxum ultra	-	2008
7179	WET	SPIN ETCHER	Lam Research	RST201	200	1996

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7240	WET	SPIN ETCHER	Lam Research	RST201	200	1997
9061	CVD	CVD	Lam (IBNOVELLUS)	CONCEPT ONE	125	1998
7706	METROLOGY	DUV DEFECT INSPECTION	Leica	INS3000	200	2001
7490	DICING	UV IRRADIATION SYSTEM	LINTEC	RAD-2000M/6	150	2005
7513	DICING	UV IRRADIATION SYSTEM	LINTEC	RAD-2000m/8	200	2006
7512	MOUNTING	WAFER MOUNTER	LINTEC	RAD-2500m/8	200	2007
8423	METROLOGY	FILM THICKNESS MEASUREMENT	Nanometrics	NanoSpec	150	1985
8453	METROLOGY	FILM THICKNESS MEASUREMENT	Nanometrics	NanoSpec	150	1984
8422	METROLOGY	FILM THICKNESS MEASUREMENT	Nanometrics	NanoSpec	150	1985
7389	METROLOGY	FILM THICKNESS MEASUREMENT	Nanometrics	NanoSpec6100	200	1998
8245	METROLOGY	FILM THICKNESS MEASUREMENT	Nanometrics	NanoSpec9200	200	2001
7338	METROLOGY	FILM THICKNESS MEASUREMENT	Nanometrics	NanoSpec9310	200/300	2008
7432	CMP	CMP	Okamoto	SPP-600S GRIND	125	1998
7568	WET	SUPERCritical RINSE&DRYER	Rexxam	SCRD6	150	2008
8216	CMP	CMP-OXIDE	RORZE	Mirra Fabs & FI	200	1998
7239	METROLOGY	FILM THICKNESS MEASUREMENT	Rudolph	S200ETCH	200	2000
7263	WET	POST CMP CLEANING SYSTEM	SCREEN	AS2000	200	1998
8391	WET	POST CMP CLEANING SYSTEM	SCREEN	AS2000	200	1998
7622	WET	POST CMP CLEANING SYSTEM	SCREEN	AS2000	200	2000
7994	WET	WET STATION	SCREEN	CW-2000	200	-
7209	WET	WAFER SCRUBBER	SCREEN	SS-W80A-AR	200	1995
7211	WET	WAFER SCRUBBER	SCREEN	SS-W80A-AVR	200	1998
7425	METROLOGY	FILM THICKNESS MEASUREMENT	SOPRA	GESP5	200	1998
7495	METROLOGY	AUTOMATIC VISUAL INSPECTION	TAKANO (TOPCON)	Vi-4202	200	2004
7467	BACK GRIND	TAPE REMOVER	Takatori	AMR-2200G	200	-
7860	FURNACE	FURNACE_DIFFUSION	TEL	Alpha-8SE	200	2005
7288	FURNACE	FURNACE_LP-CVD	TEL	IW-6C	150	1994
7993	PHOTOLITHO	COATER	TEL	MARK-8	200	1996
8464	PHOTOLITHO	COATER&DEVELOPER	TEL	MARK-V	200	1992
7431	PHOTOLITHO	COATER&DEVELOPER	TEL	MARK-Vz	150	1998
8270	WET	WAFER SCRUBBER	TEL	SS-4	200	2001
8440	ETCH	OXIDE ETCHER	TEL	TE5000ATC	150	1992
7827	ETCH	OXIDE ETCHER	TEL	TE8500(S)	150	2000
7398	ETCH	OXIDE ETCHER	TEL	TE8500(S)ATC	150	1992
8441	ETCH	OXIDE ETCHER	TEL	TE8500(S)ATC	150	1993
8248	ETCH	OXIDE ETCHER	TEL	TE8500(S)ATC	200	1995
7252	ETCH	OXIDE ETCHER	TEL	TE8500ATC	200	1995
7571	ETCH	OXIDE ETCHER	TEL	Unity Me 85D	200	2003
7339	ETCH	OXIDE ETCHER	TEL	UnityII-855II	200	1996
7889	ETCH	OXIDE ETCHER	TEL	UnityIle-655PP	150	2000
7853	ETCH	OXIDE ETCHER	TEL	UnityIle-855SS	200	2006
8061	ASHER	ASHER	TOK	TCA-3822	200	1995
7408	ASHER	ASHER	TOK	TCA-3822	200	1995
8352	ETCH	OXIDE ETCHER	TOK	TCE-3822	200	-
8351	ETCH	OXIDE ETCHER	TOK	TCE-3822	200	-

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7619	PHOTOLITHO	WAFER EDGE EXPOSURE	Ushio	PE-250R2HK	200	-
7620	PHOTOLITHO	WAFER EDGE EXPOSURE	Ushio	PE-250T2HM	200	-

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